Application Serial No. 10/565,621 Response to Office Action of March 12, 2009 Reply dated, September 11, 2009

Amendment to the Specification:

On page 11, please replace the paragraph beginning at line 19 with the following amended paragraph:

Figure 6 represents a fifth step of that method[[.]].

On page 11, after line 19, please add the following paragraph:

Figure 7 illustrates the silicon plate of Figure 3, having a non-continuous sacrificial layer.

On page 16, please replace the paragraph beginning at line 26 with the following amended paragraph:

It is clear that a non-continuous sacrificial layer <u>3</u> may be obtained <u>as shown in Figure </u><u>7</u>, for example by localized deposition or by etching; this enables areas already opened up to be defined in the stacked structure.